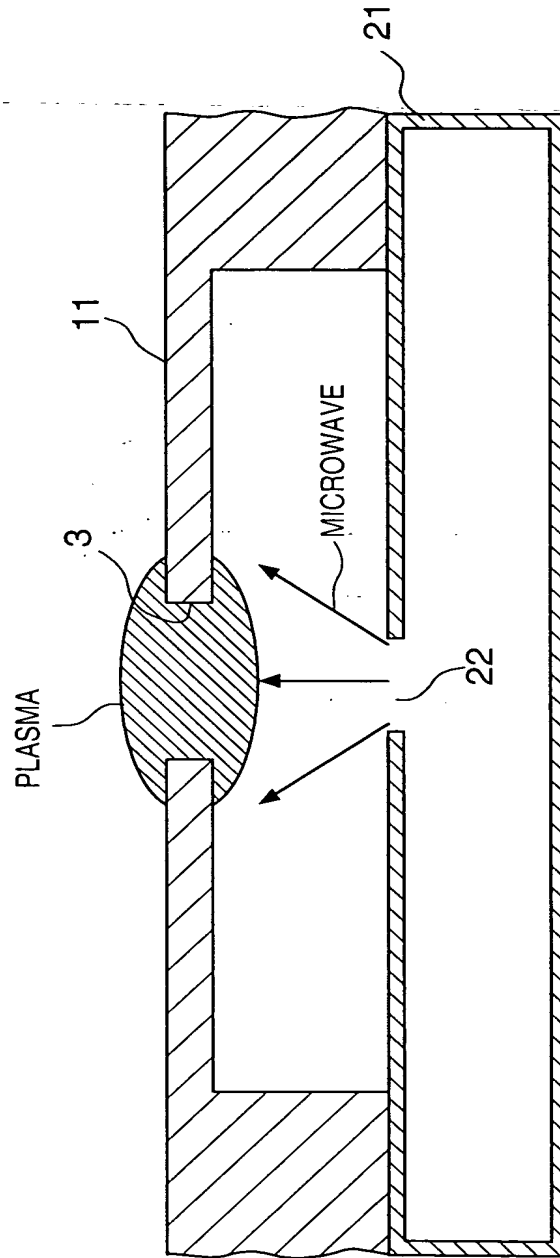


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FIG. 1



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FIG. 2A

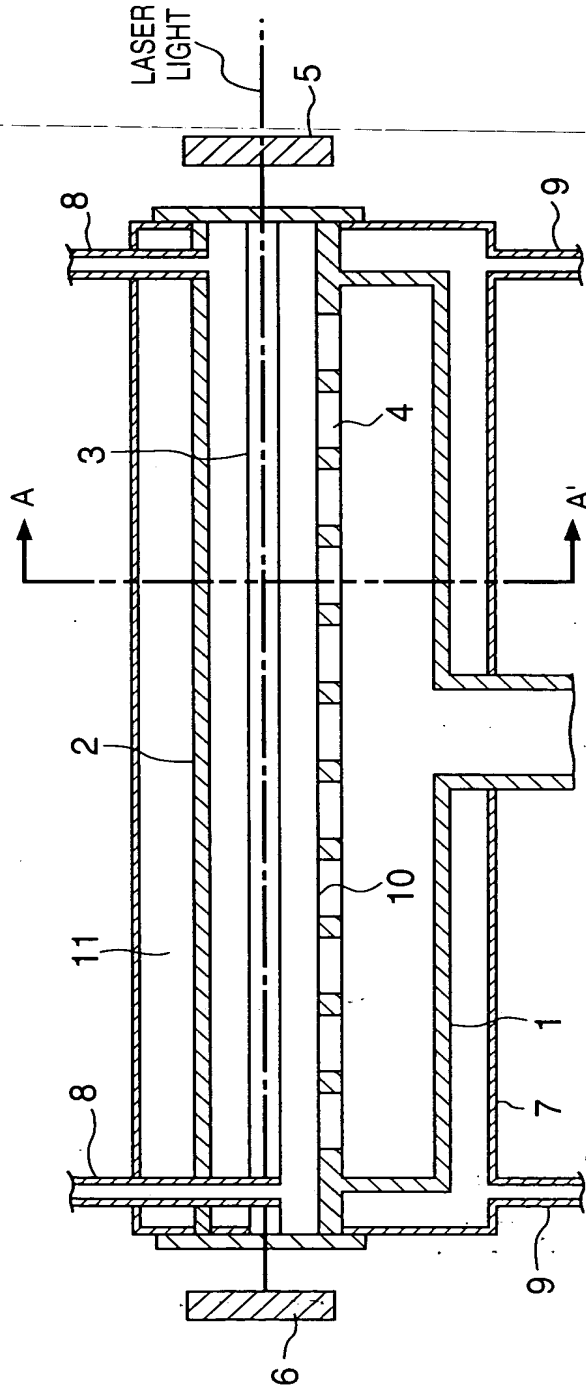


FIG. 2B

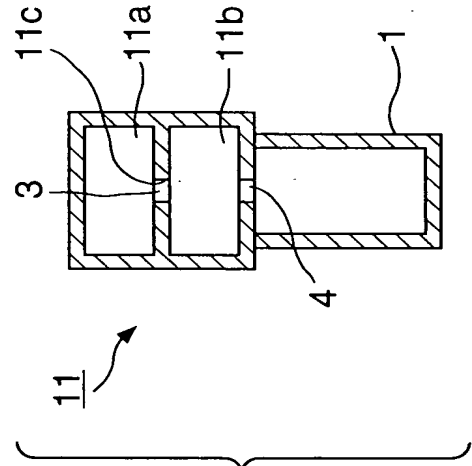
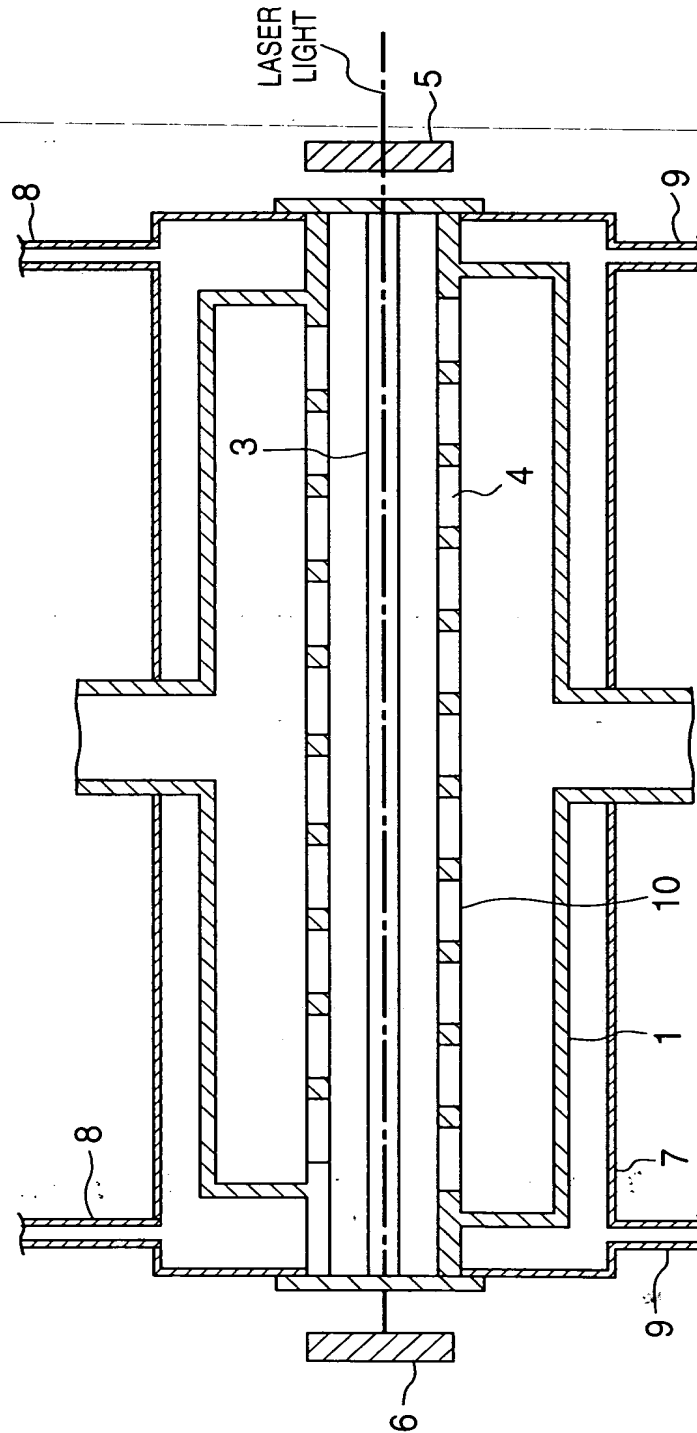


FIG. 3



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FIG. 4A

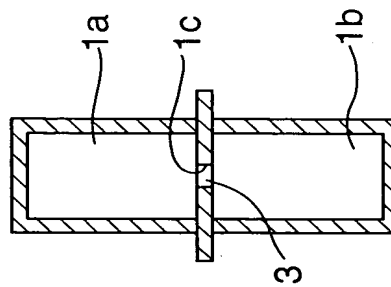
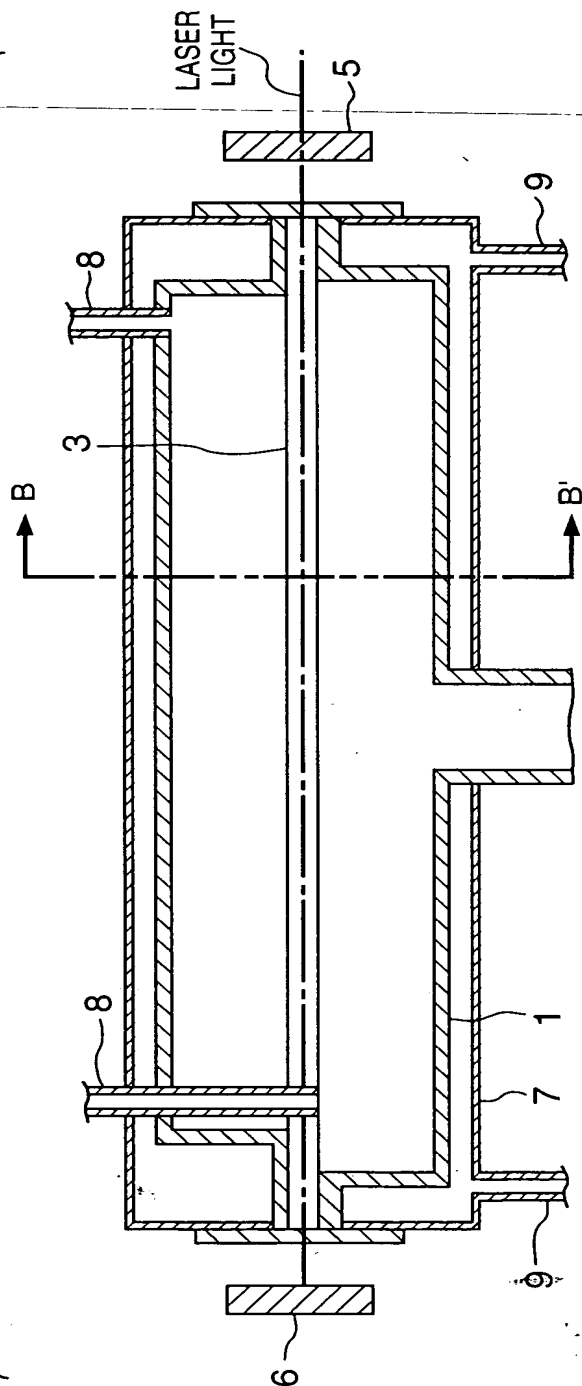
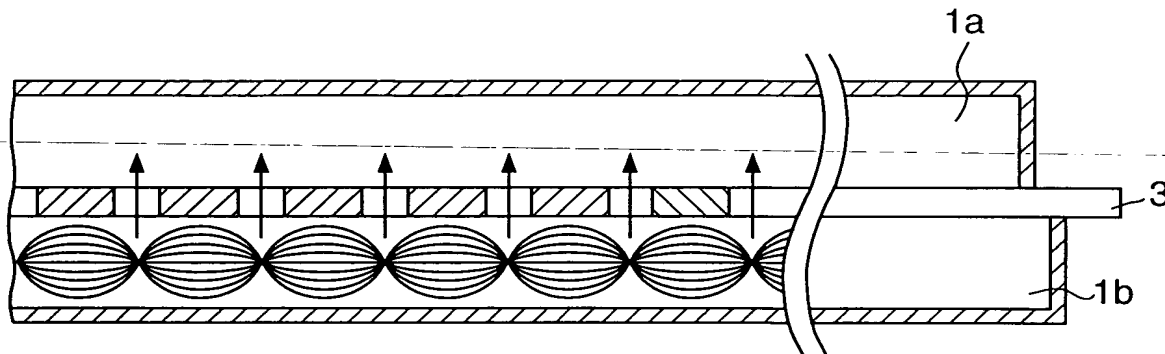


FIG. 4B

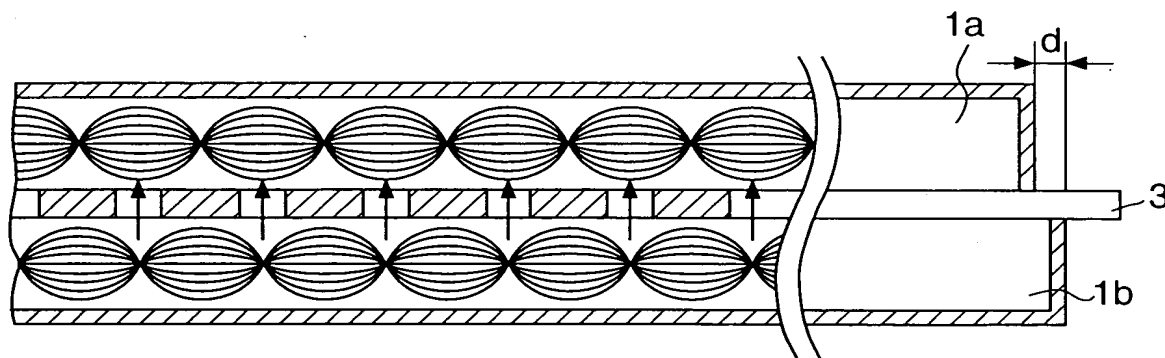
## FIG. 5A

ACTION IN INPUT-SIDE WAVEGUIDE PLASMA



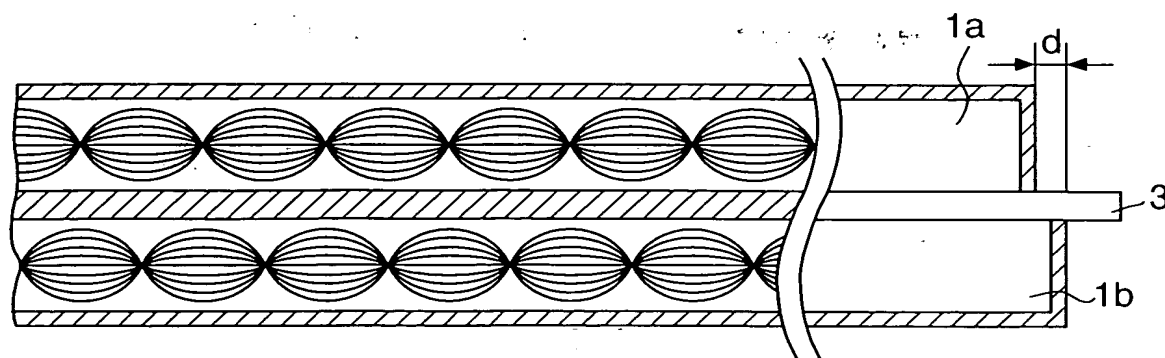
## FIG. 5B

ACTION FROM PLASMA NON-EXCITED POSITIONS  
STANDING WAVE IN RESONANCE WAVEGUIDE BY LEAKAGE TO WAVEGUIDE



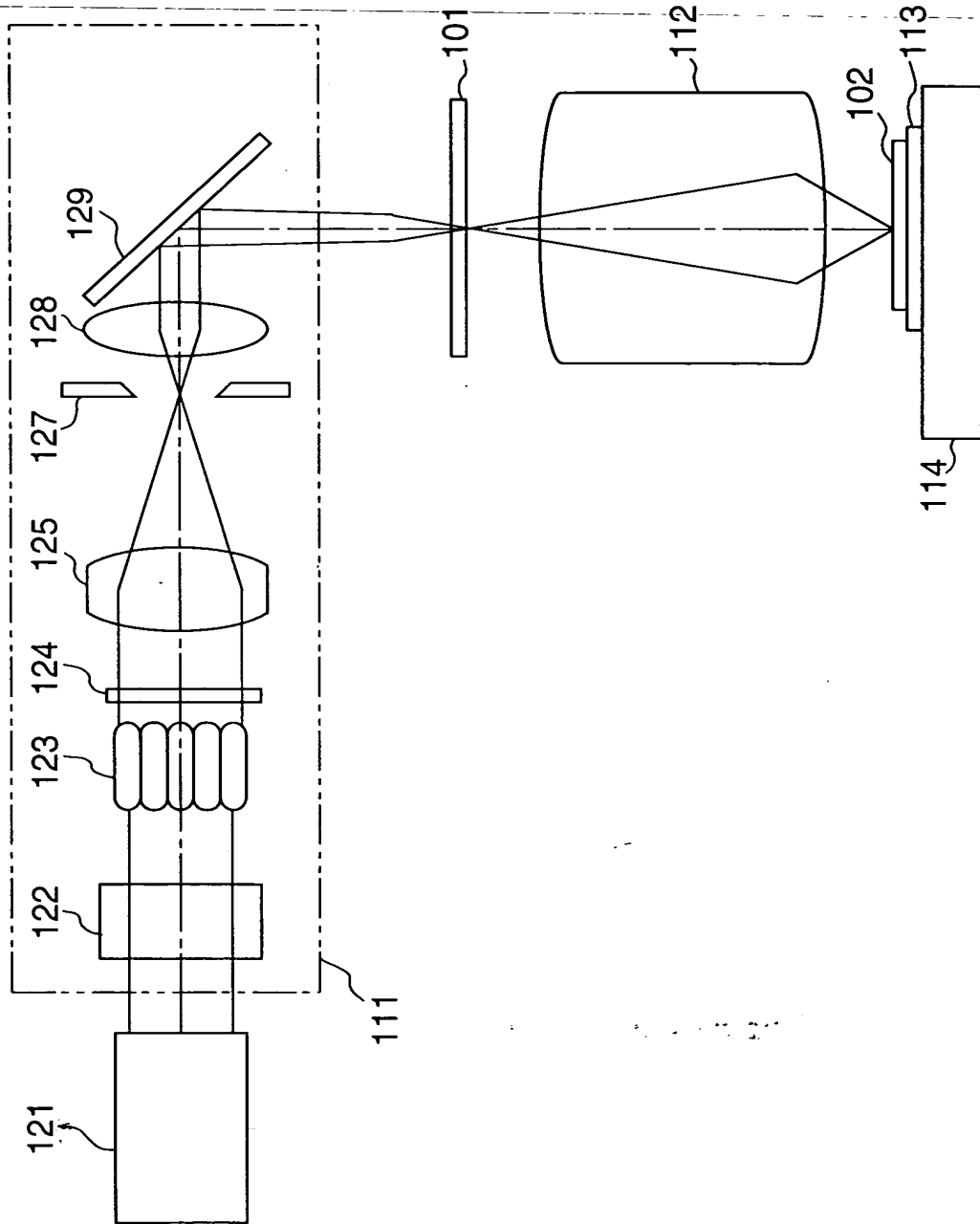
## FIG. 5C

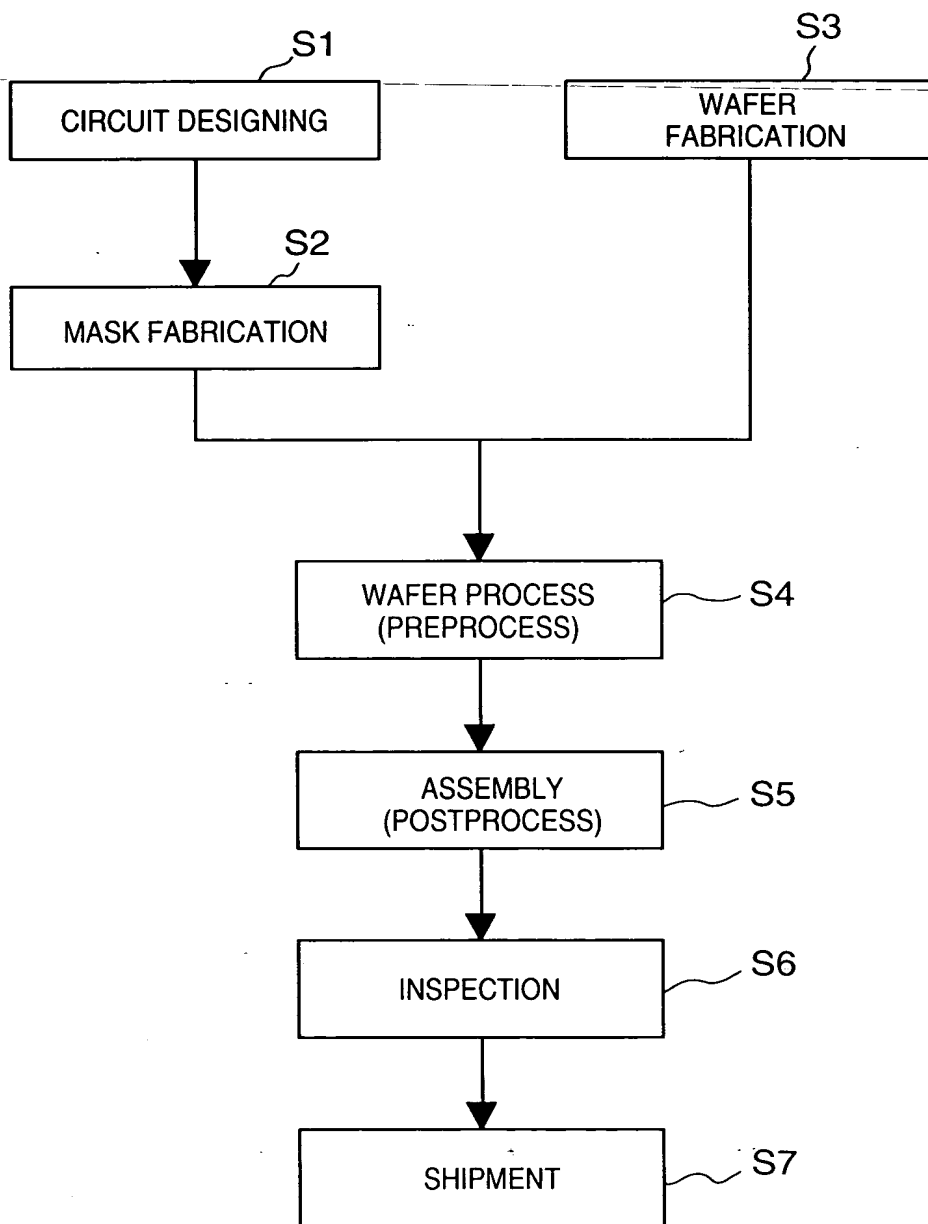
INTERPOLATION IN PLASMA  
EXCITATION SPACE USING STANDING WAVE IN RESONANCE WAVEGUIDE



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FIG. 6

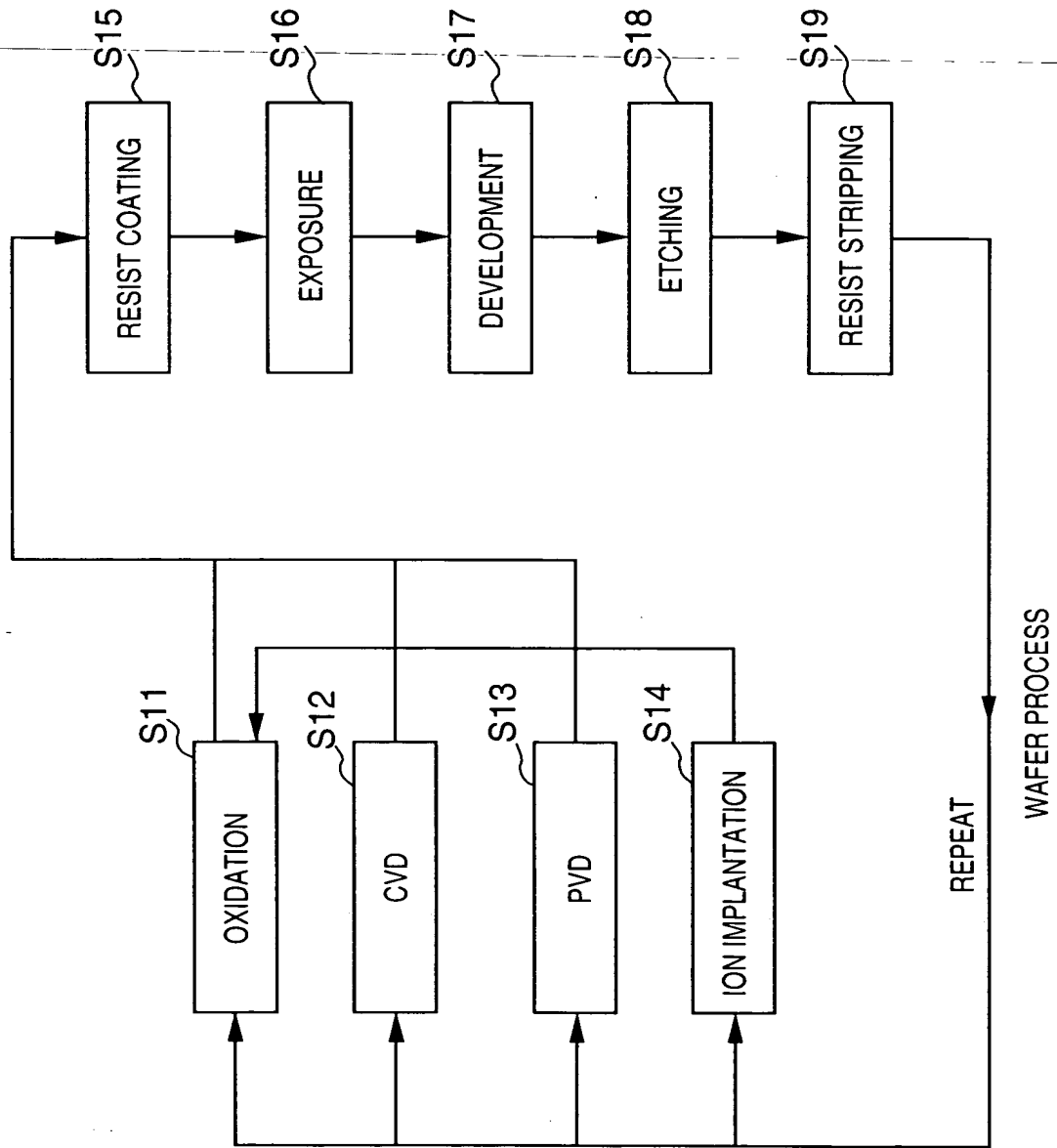


**FIG. 7**

SEMICONDUCTOR DEVICE FABRICATION FLOW

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FIG. 8



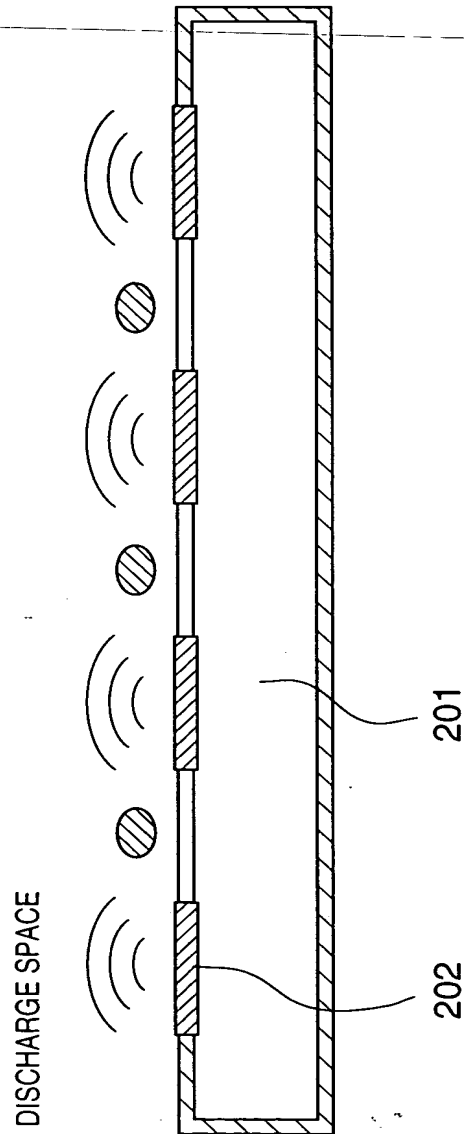
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FIG. 9



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